

Solving the Information Technology Challenges Beyond Moore's Law

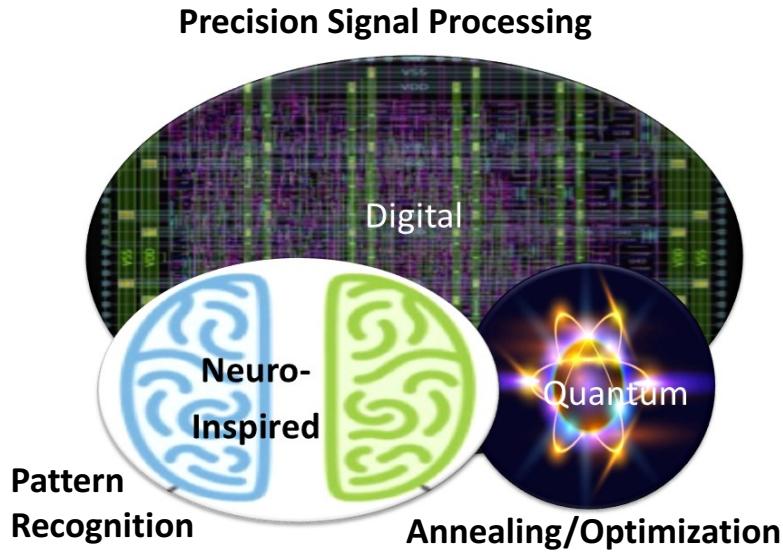
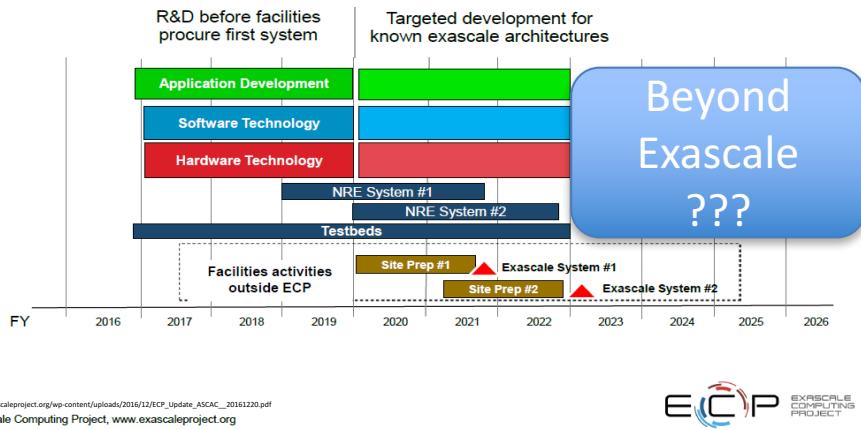
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SAND2017-11048C

Beyond Moore's Law Computing (BMC)

High-level ECP technical project schedule



What is “Beyond Moore’s Law”?

- **Litho scaling costs accelerating**
- **Techno-economic agreement dissolving**
- **“More-Moore’s Law” progress for the next 5+ years? (HI, 3D, PIM, CMOS specialization)**
- **Looming disruptive event on the 5-10yr horizon**

Semiconductor industry is huge economic driver

\$56 Billion
Semiconductor
R&D and Cap Ex
(2013)

\$336 Billion
Semiconductor
device market
(2014)

*US Semi tool vendor profits now declining,
Consolidated: 24 companies ('95) → 2 today*

*Only 1 US leading edge Fab Co (of 4 total)
US market share: ~75% ('95) → ~50% today*

*China/Asia = ~70% of
consumer electronics
production*

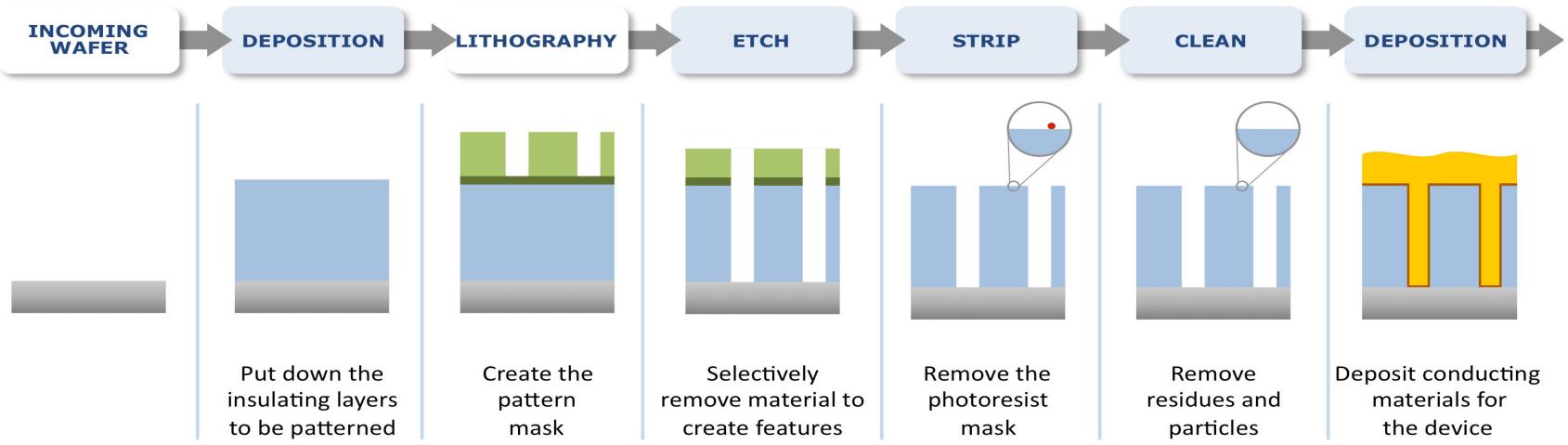
\$2.3 Trillion
Global electronics
market (2014)

SIA, www.globalsmt.net

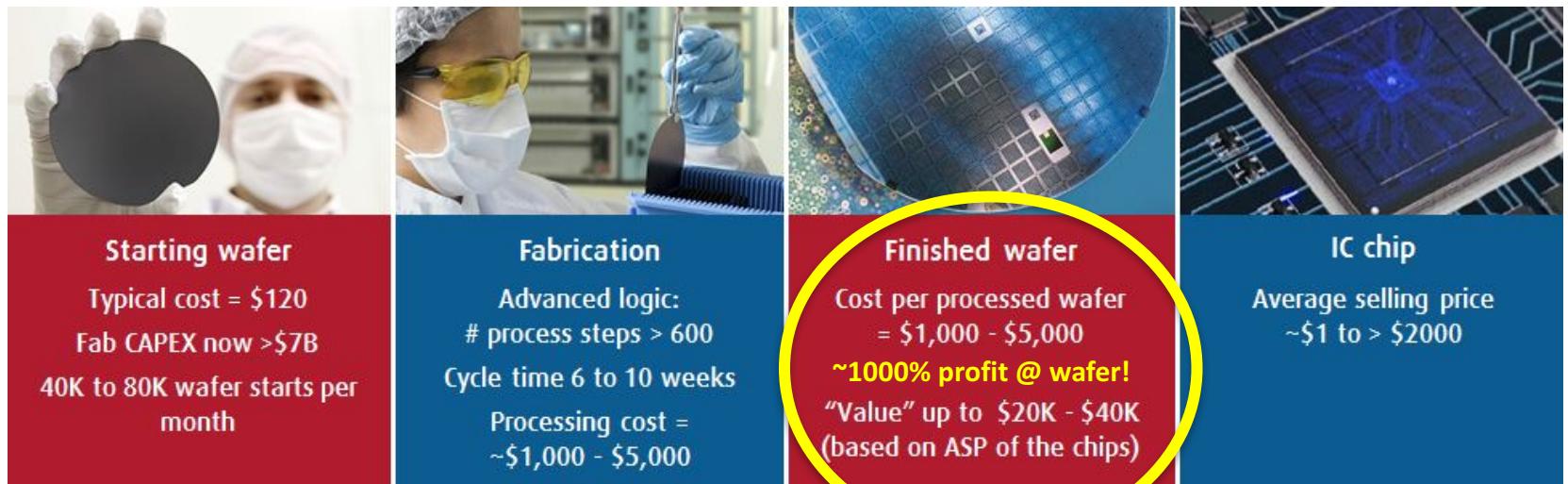
The semiconductor industry is crucial to the U.S. economy. Semiconductor sales constitute a \$336B/yr. economic engine driving the \$2.3T/yr. global electronics industry. Semiconductor products are currently the second largest class of U.S. exports

Silicon Integrated Circuit Fab

WAFER FABRICATION PROCESS STEPS

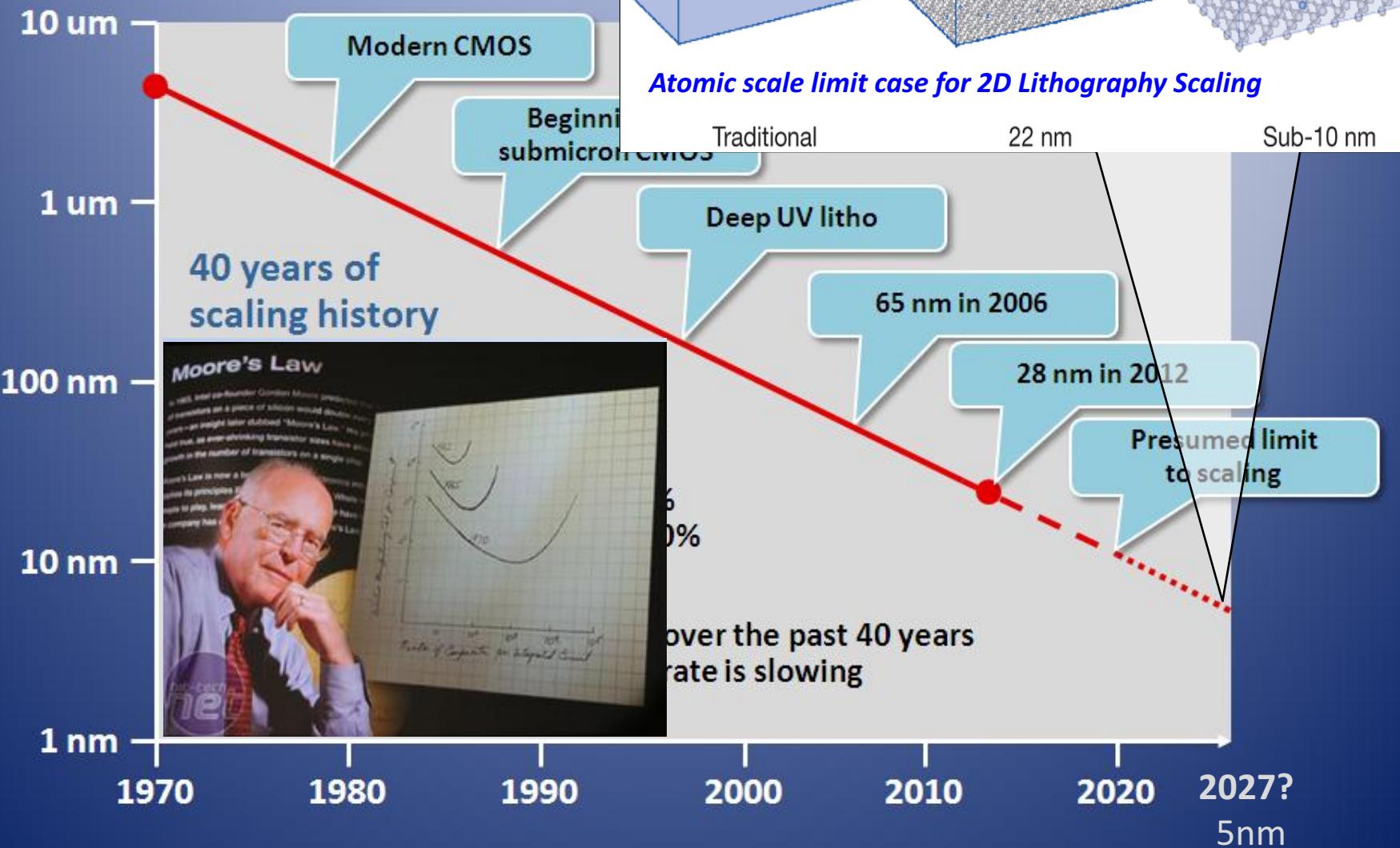


http://www.lamresearch.com/portals/0/Images/Wafer_Fabrication_Process_Steps.jpg



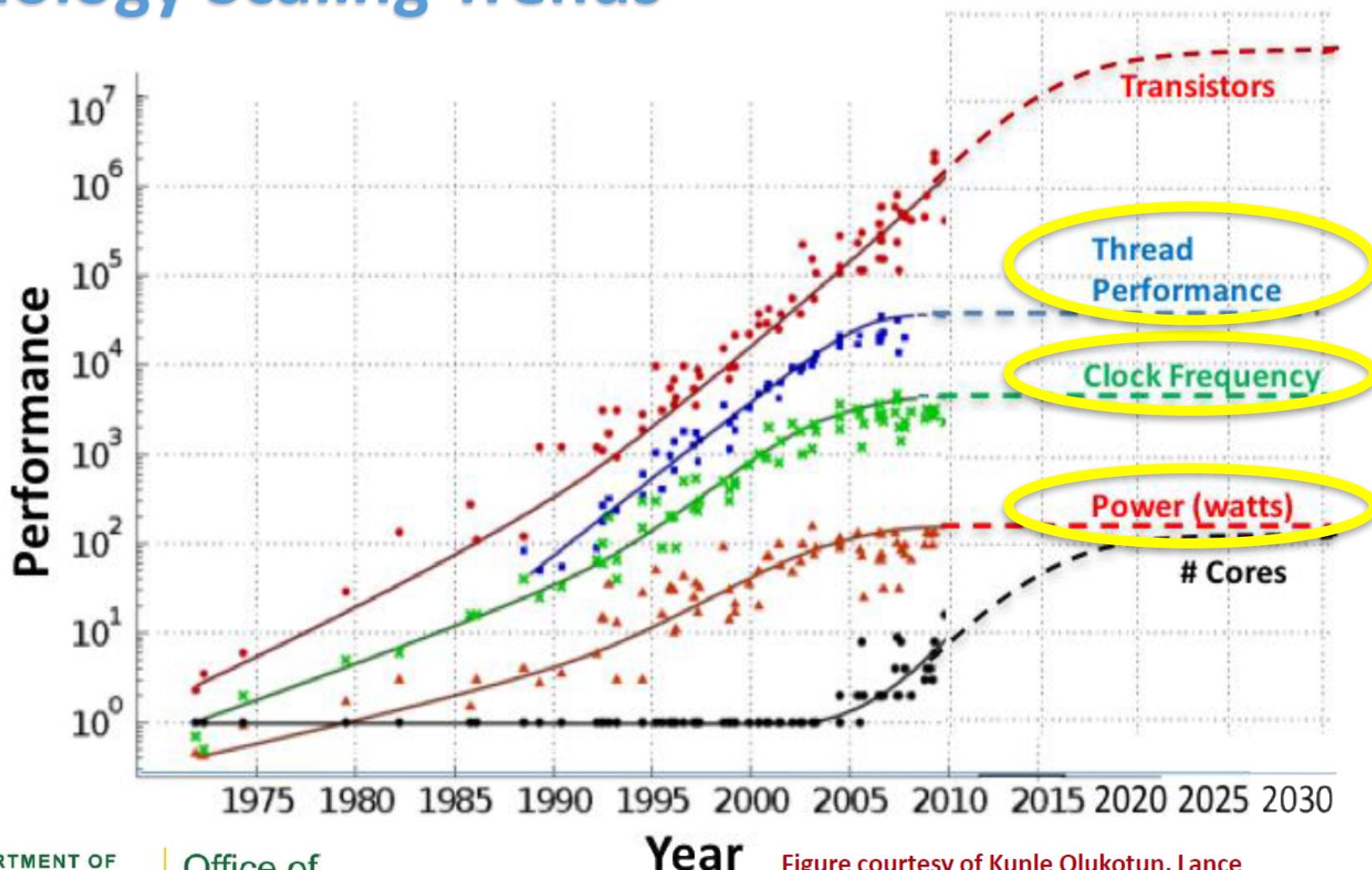
<http://semimd.com/materials-matters/files/2015/08/Costs-of-wafer-to-IC-chip.jpg>

50 years of Sem



End of Moore's law: technology

Technology Scaling Trends



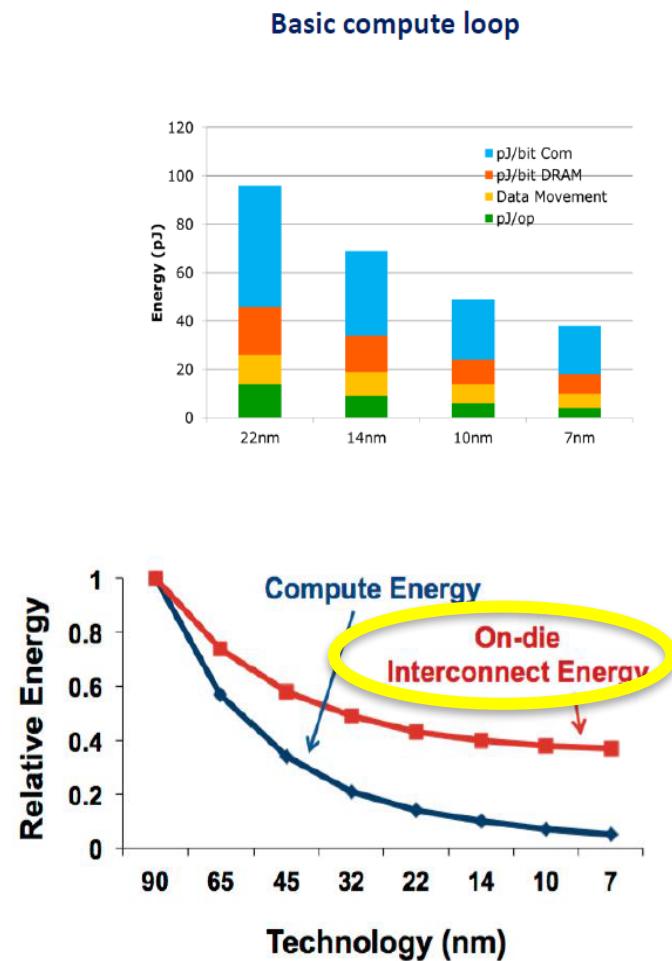
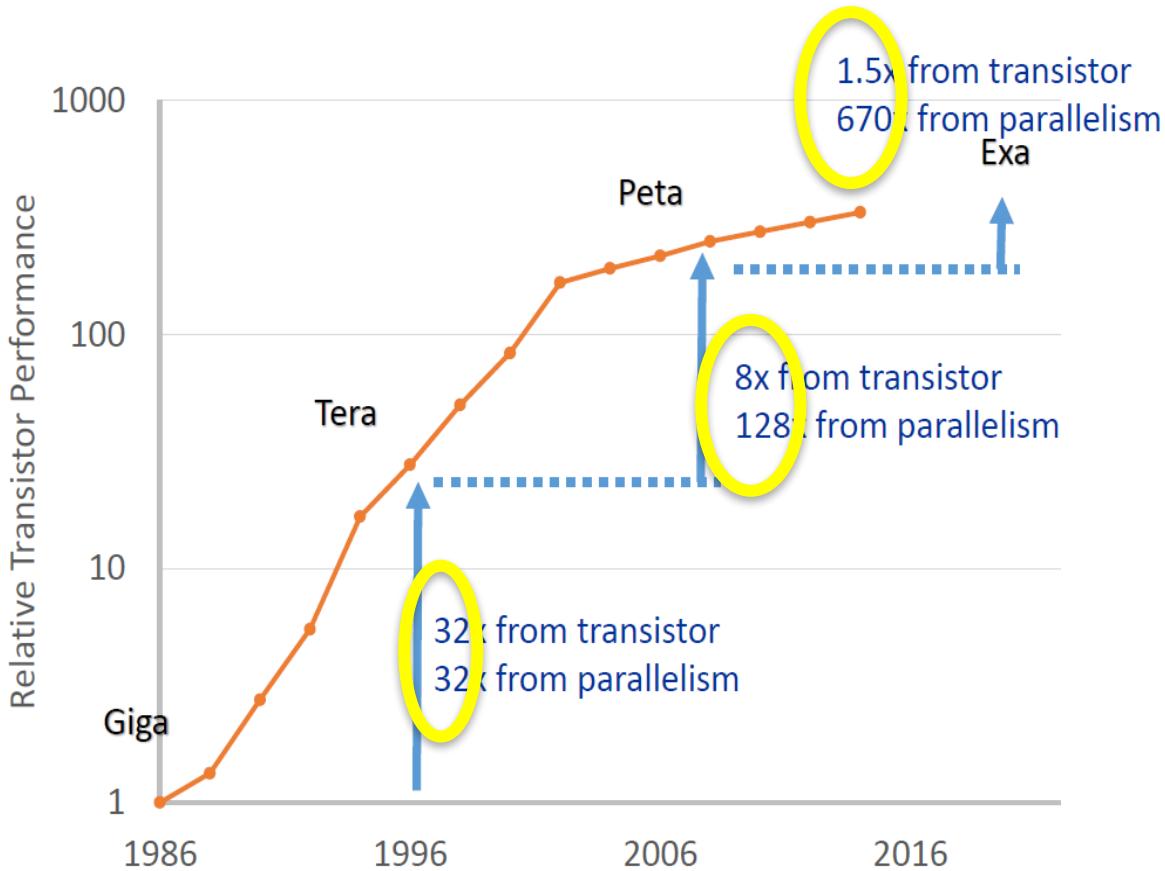
U.S. DEPARTMENT OF
ENERGY

Office of
Science

Figure courtesy of Kunle Olukotun, Lance
Hammond, Herb Sutter, and Burton Smith

End of Moore's law: technology

From Giga to Exa, via Tera & Peta



End of Moore's law: economics

designlines MCU

News & Analysis

Samsung Breaks Ground on \$14 Billion Fab

World's most expensive semi fab

R. Colin Johnson
5/8/2015 03:18 PM EDT
14 comments



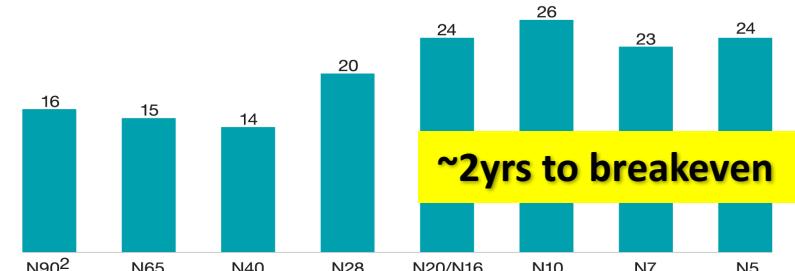
Figure 4: Fab Costs by Node (in US\$ billions)



Source: Common Platform Technology Forum 2012 and AlixPartners analysis

Payback time for foundries will be close to 24 months for nodes smaller than 20 nanometers/16 nanometers.

Investment payback time, months¹



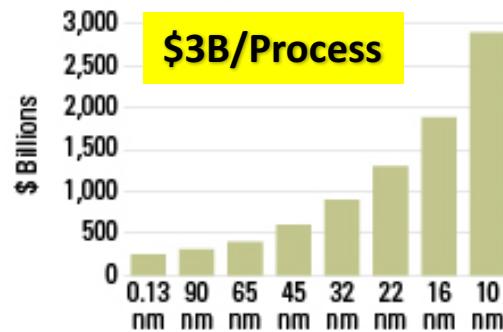
¹Includes fab capital expenditures and R&D.

²N = node.

McKinsey&Company

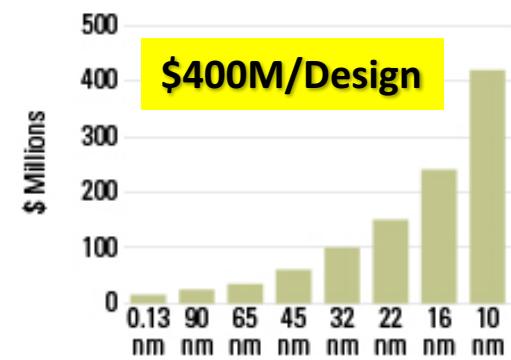
<http://www.mckinsey.com/~/media/McKinsey/Industries/Semiconductors/Our%20Insights/Capital%20equipment%20Will%20further%20shrink%20bring%20growth/PNG%20Capital%20equipment%20ex%203.ashx>

Figure 5: Process Technology Development Costs by Node (US\$ billions)



Source: Common Platform Technology Forum 2012 and AlixPartners analysis

Figure 6: Chip Design Costs by Node (US\$ millions)



Source: Common Platform Technology Forum 2012 and AlixPartners analysis

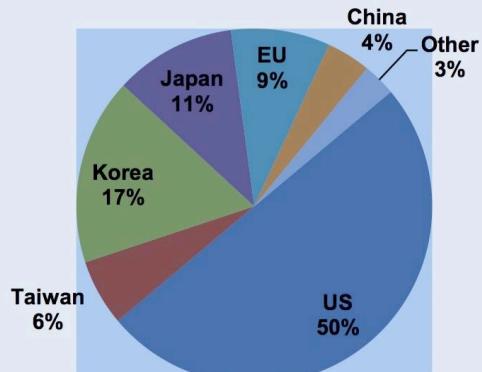
<http://legacy.alixpartners.com/en/Portals/alix/IC%20Copy%20&%20Images/High-Tech/2014%20Cashing%20in%20with%20Chips/04-05-06-SEMICONDUCTOR-0114.jpg>

Beyond Moore's Law Computing (BMC)

Global Drivers...the Problem & the Opportunity

Global Competition & Market Share

Figure 2: Global Market Share of Semiconductor Production, 2015



Source: SIA/World Semiconductor Trade Statistics (WSTS)/IHS/PwC/IC Insights
Share based on headquarters of seller: Foundry output not included, fabless included.

China: \$120B-\$150B Investment

National Security

Sunway TaihuLight : June 2016
Worlds Fastest Computer
An Indigenous Chinese Computer
Dropped Power Consumption by ~25%



Energy Consumption



Semiconductor Industry Association, 2015-2017



December 18, 2015

President Barack Obama
The White House
1600 Pennsylvania Avenue NW
Washington, DC 20500

Dear Mr. President:

I am writing on behalf of the U.S. semiconductor industry to urge you to take several important actions to help ensure continued U.S. leadership in semiconductor technology. These recommendations are in response to requests from officials in your Administration for suggested actions to address the challenges that recent Chinese policies and actions pose to our industry.

A horizontal banner for the SIA 2017 Policy Priorities. The background is a blue-toned image of a circuit board. The SIA logo is at the top left. The word 'SEMICONDUCTORS' is in large white capital letters, with 'Building America's Innovation Economy' in smaller text below it. A sub-headline says 'Maintaining a vibrant U.S. semiconductor industry is strategic to America's continued strength.' Below this is a section titled '2017 POLICY PRIORITIES' with two main points: 'TAX – Make the U.S. Tax System Globally Competitive' and 'RESEARCH – Increase Federal Investment in Semiconductor Research'. Each point has a list of actions.

Research: The semiconductor industry has followed Moore's Law to unimaginable levels, enabling smaller, more powerful and energy-efficient devices while reducing costs to consumers. Our industry annually invests about one-fifth of revenue in R&D, a greater share than any other industry. We will continue to **urge government to serve as a partner** in this effort by substantially increasing federal investments in university-based, **pre-competitive research at DARPA, NIST, NSF, and DOE.** We'll also push policymakers to implement and support research programs to advance semiconductor technology and innovation.



U.S. Leadership in High Performance Computing (HPC)

A Report from the NSA-DOE Technical Meeting on

High Performance Computing

December 1, 2016

To maintain and extend U.S. leadership in HPC, it is **critical to lead the exploration and development of innovative computing architectures** that will unleash the creativity of the HPC community.....participants recommend the U.S. engage in innovative architectural exploration and development...

This will require a strong and sustained commitment to **a variety of architectural approaches**, where each is clearly focused on a reasonable subset of clearly important applications (e.g., **modeling and simulation, large-scale analytics, cybersecurity**, etc.). Multiple teams, each capable of developing novel computing architectures **using a complete co-design approach**, will be required....Fully functional **system prototypes** from these explorations will need to be developed and evaluated for their specific application subset. **Technology advancements** common to many (or all) architectures will also **need to be supported** (i.e., **new memories, silicon photonics, programming tools and languages, etc.**).

PCAST Study Group, 2017

REPORT TO THE PRESIDENT Ensuring Long-Term U.S. Leadership in Semiconductors

Executive Office of the President
President's Council of Advisors on
Science and Technology

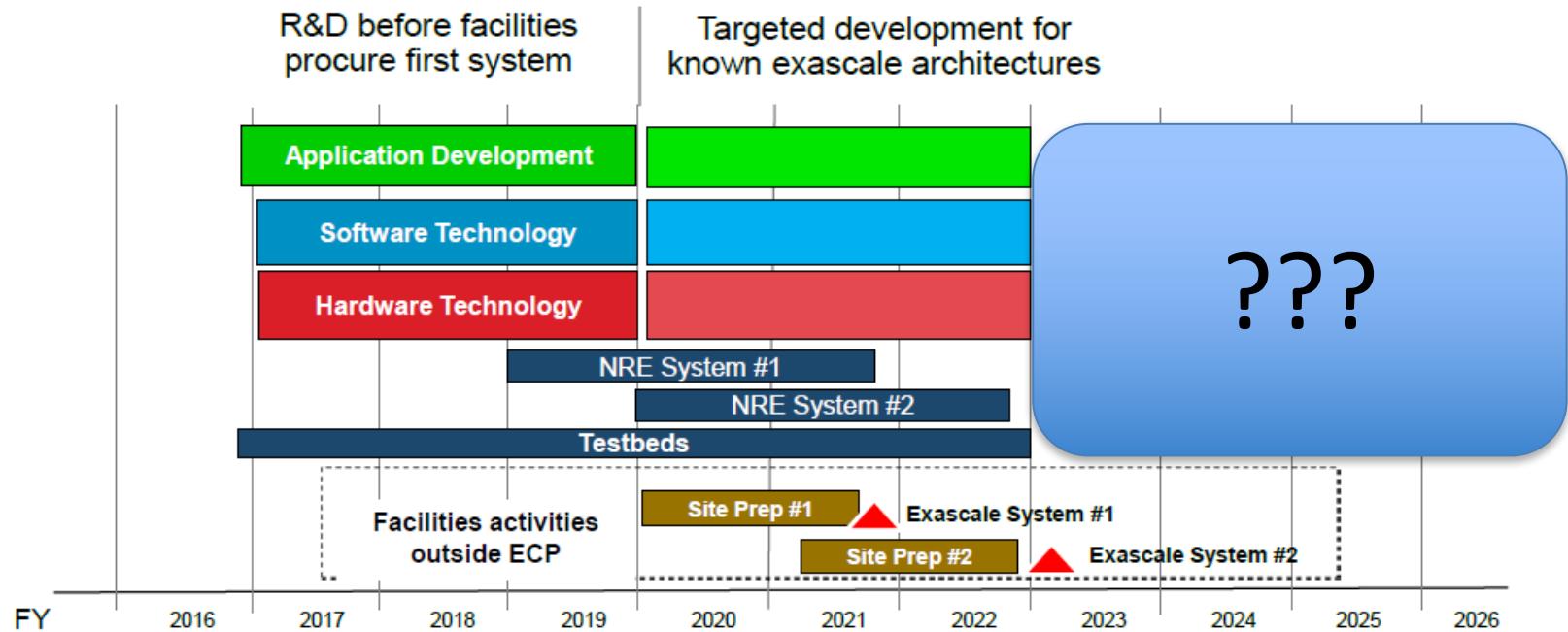


January 2017

“The core finding of the report is this:...to mitigate the **threat posed by Chinese industrial policy** and strengthen the U.S. economy. Thus, the report recommends and elaborates on a three pillar strategy to (i) push back against innovation-inhibiting Chinese industrial policy, (ii) improve the business environment for U.S.-based semiconductor producers, and (iii) **help catalyze transformative semiconductor innovation over the next decade. Delivering on this strategy will require cooperation among government, industry, and academia to be maximally effective.**”

How will DOE build HPC AFTER Exascale?

High-level ECP technical project schedule



https://exascaleproject.org/wp-content/uploads/2016/12/ECP_Update_ASCAC__20161220.pdf

9 Exascale Computing Project, wwwexascaleproject.org



Challenges are increasing and Moore's law is ending:

How can we prepare for technology disruption in the next phase?

20fJ/Instruction Impact

PetaScale
2016: 40nJ/FLOP



ExaScale
2022: 20pJ/FLOP



ZettaScale
2030: 20fJ/Instr

Energy-efficient electronics enable a spectrum of key Mission Applications

ZettaFLOP HPC in 20MW

Full scale high-fidelity modeling



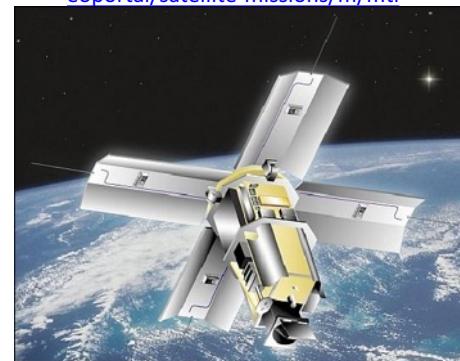
<http://www.deccanchronicle.com/technology/in-other-news/200616/new-chinese-system-named-worlds-top-supercomputer.html>

100 PFLOP in 2KW, Design Cluster
Model-based component design

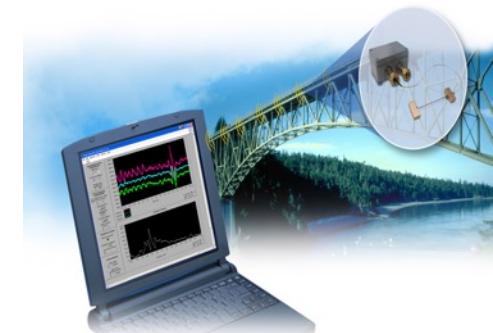


<https://blog.cr.yp.to/20140602-saber.html>

<https://directory.eoportal.org/web/eoportal/satellite-missions/m/mti>

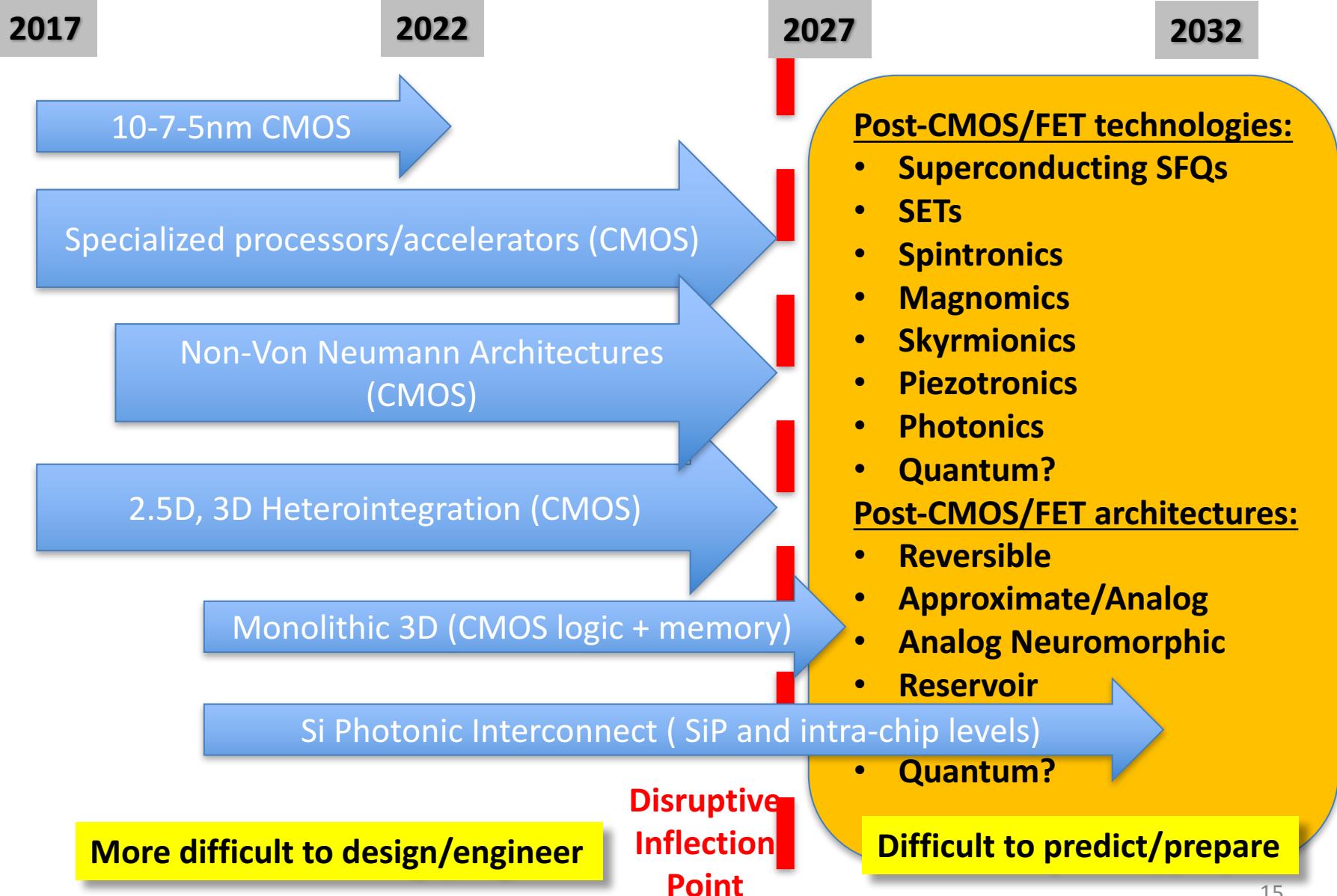


1 PFLOP in 20W
Embedded Cognitive Processor
Autonomous satellite/UAV

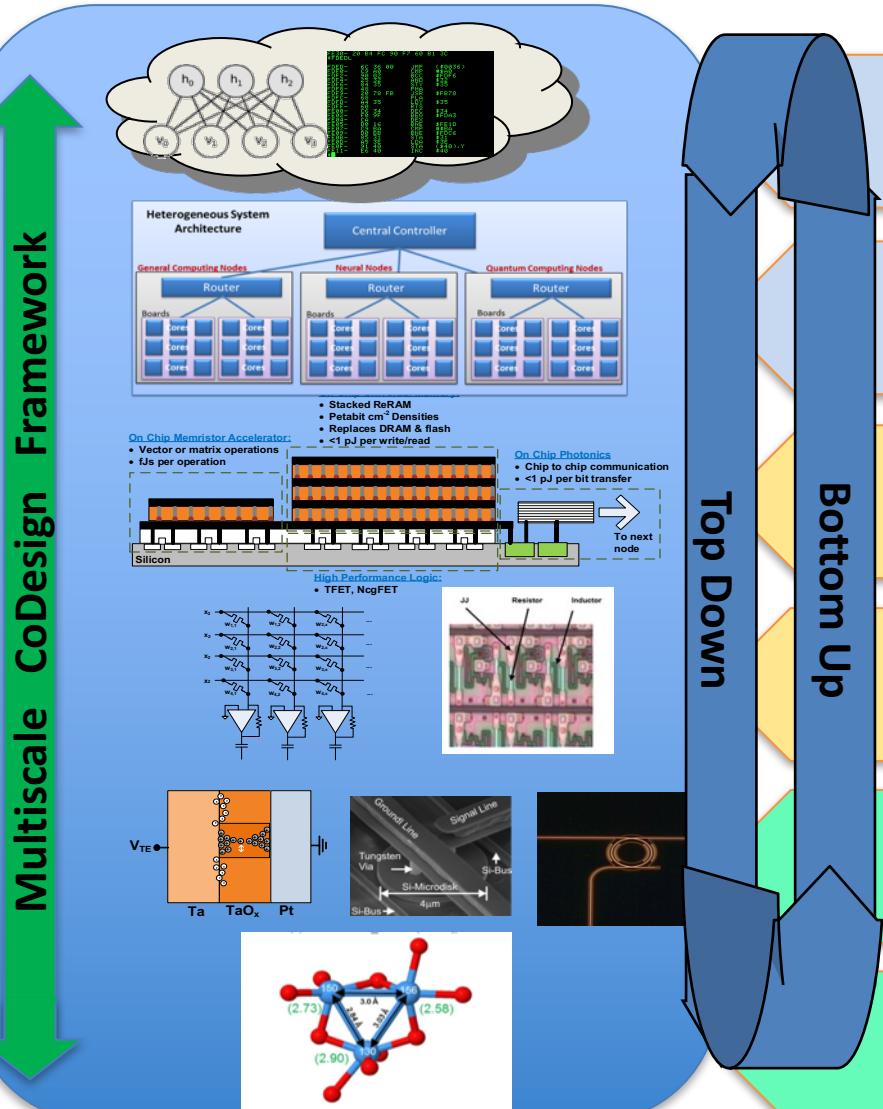


https://www.nsf.gov/discoveries/disc_images.jsp?ctn_id=108363&org=NSF Credit: MicroStrain, Inc.

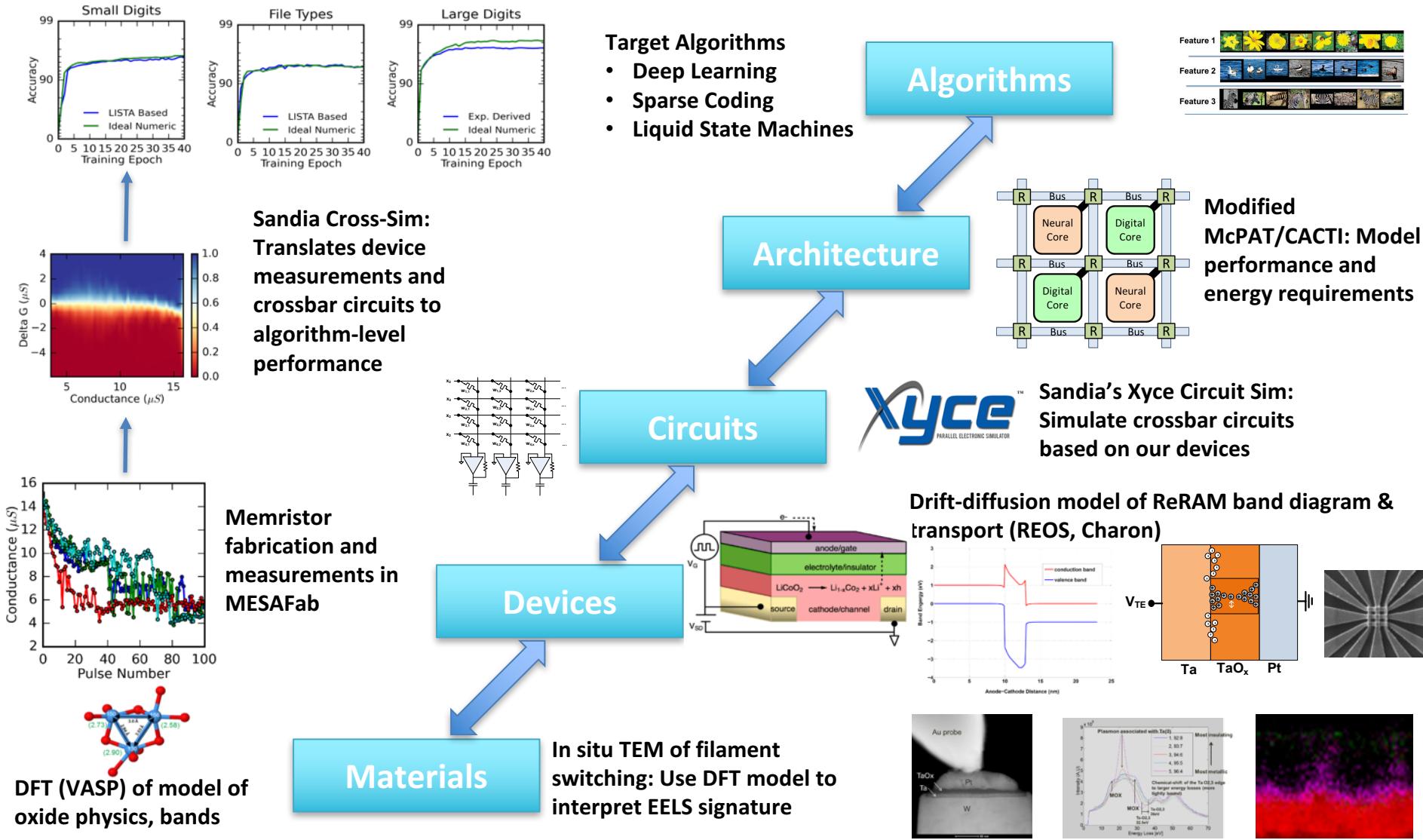
Moore's, "more-Moore's", & BMC



DOE Approach: Multiscale CoDesign



Novel Device Multiscale CoDesign Example: HAANA Crossbar Accelerator



Beyond Moore Co-design Framework: 5 Working Groups

Modeling

10,000x improvement: 20 fJ per instruction equivalent

Experimental

Algorithms and Software Environments

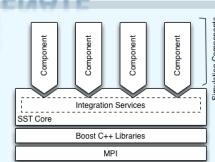
- Application Performance Modeling



CENATE

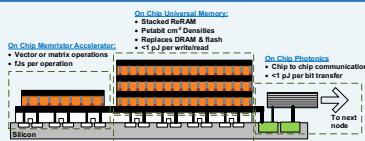
Computer System Architecture Modeling

- Next generation of Structural Simulation Toolkit
- Heterogeneous systems HPC models



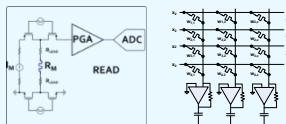
Microarchitecture Models

- McPAT, CACTI, NVSIM, gem5



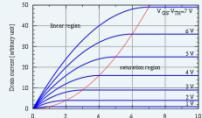
Circuit/IP Block Design and Modeling

- SPICE/Xyce model



Compact Device Models

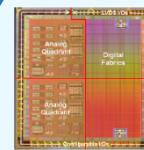
- Single device electrical models
- Variability and corner models



Device Physics Modeling

- Device physics modeling (TCAD)
- Electron transport, ion transport
- Magnetic properties

Architectures



Algorithms

Component Fabrication

- Processors, ASICs
- Photonics
- Memory

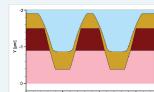


Test Circuit Fab and Measurement

- Subcircuit measurement

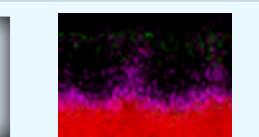
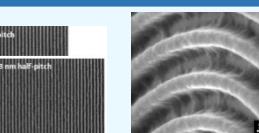
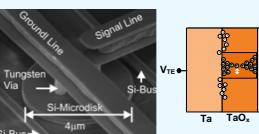
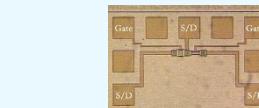
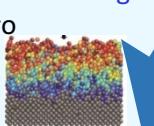
Process Module Modeling

- Diffusion, etch, implant
- Simulation
- EUV and novel lithography models



Atomistic and Ab-Initio Modeling

- DFT – VASP, Socorro
- MD – LAMMPS



Device Measurements

- Single device electrical behavior
- Parametric variability

Device Structure Integration and Demonstration

- Novel device structure demonstration

Example activities
within a MCF

Process Module Demonstrations

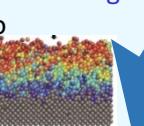
- EUV and novel lithography
- Diffusion, etch, implant simulation

Fundamental Materials Science

- Understanding Properties/Defects via Electron, Photon, & Scanning Probes
- Novel Materials Synthesis

Advanced Manufacturing

Devices



Algorithms & SW Environments

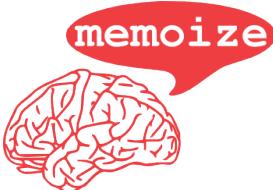
Hardware & Circuit Architectures

Comm., Memory & Computation Devices

Materials

DOE BMC Key Capabilities & Facilities: Post-Exascale Scientific Computing

*Target Application:
Physics Code*

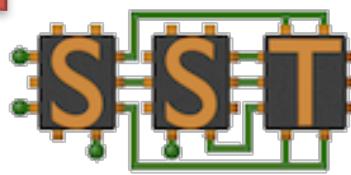


A. Rahimi, et al, In *IEEE Design & Test of Computers*, 2015

- *Novel Interconnect Networks*
- *Disaggregated memory*

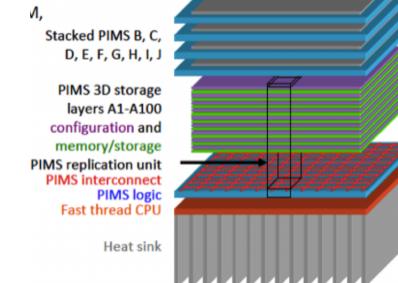


Algorithms



Architecture

Advanced Manufacturing



- *Heterogeneous Integration*
- *STT circuit Accelerators*
- *Single-electron Charge Logic*
- *Photonic Interconnect*

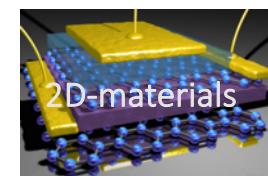
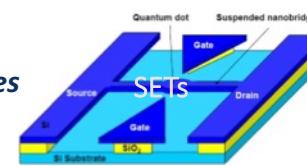


Circuits

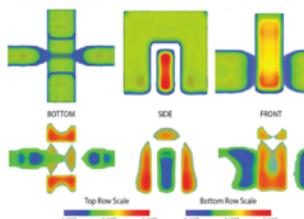


CHISEL

- *Photonics & Plasmonic devices*
- *Single Electron devices*
- *Magnetic/spin-torque RAM*

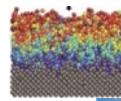


Devices



Universal
Charge
Device
Simulator

Ab Initio Models



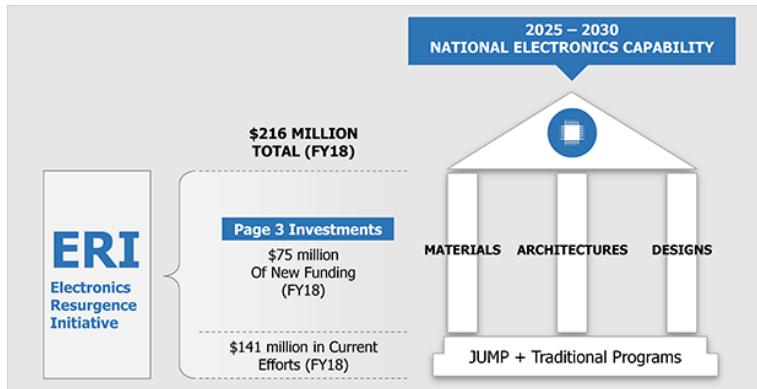
Advanced
Manufacturing



MOLECULAR
FOUNDRY



Gov't & Industry BMC Activity Increasing



C3

E₂CDA

nCORE

Are Photonic Accelerators Ready for Prime Time?

Thank you!

F. B. "Rick" McCormick
Sandia National Laboratories
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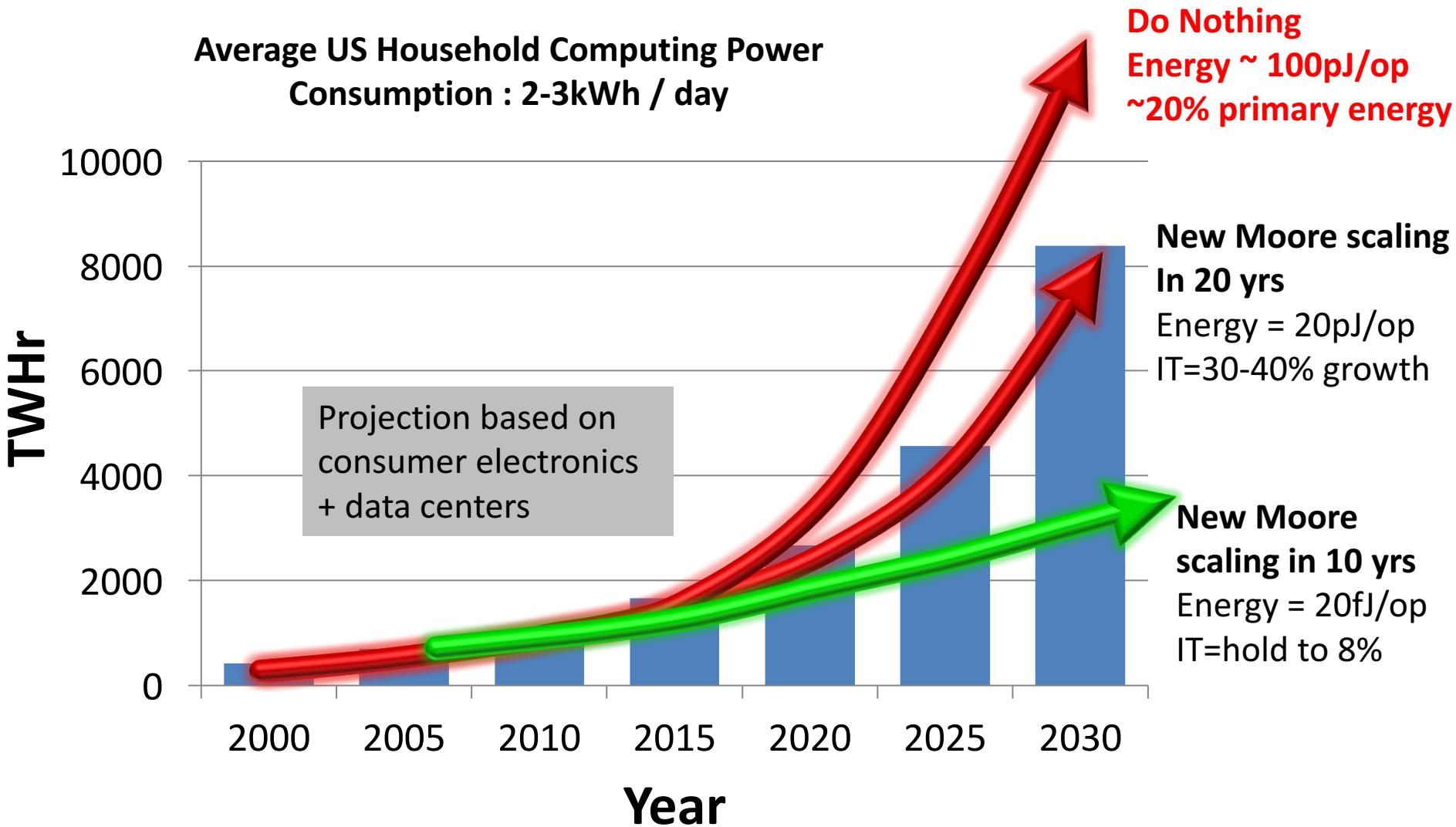
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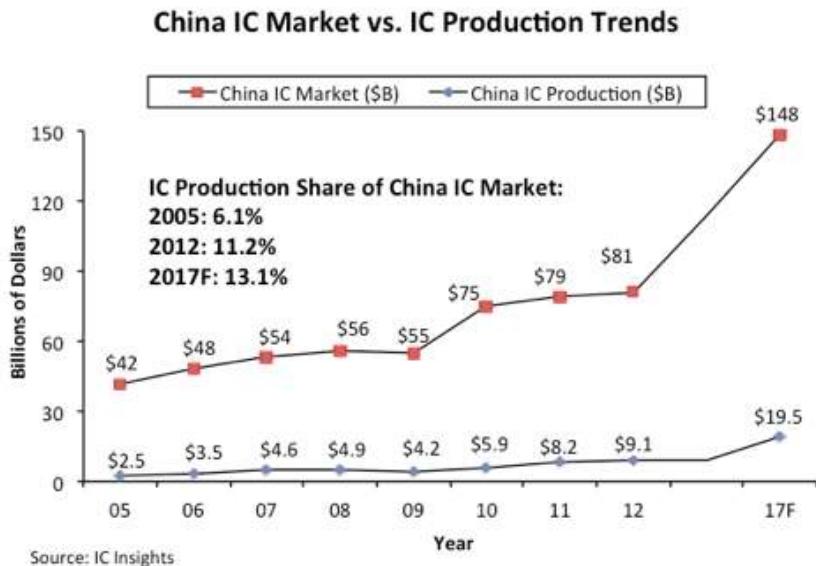
Backups

IT challenge for future electricity supply

Global Semiconductor market size ~ \$5Trillion by 2030



China: "National Guideline for Development of the IC Industry"



China created a \$19.3 billion fund, which will be used to invest in its domestic IC firms. Over the next decade, local municipalities and private equity firms could spend \$100 billion across China's IC sector.

In the 1970s, China had several state-run chipmakers, but those concerns were far behind the West in terms of IC technology. So starting in the 1980s, China began to embark on several initiatives to modernize its IC industry. The latest effort was launched in 2014, when China unveiled what it called the "National Guideline for Development of the IC Industry." The plan is to accelerate China's efforts in a number of areas, such as **14nm finFETs, advanced packaging, MEMS, memory, and various IoT-related processors.**

SMIC, Huawei, imec, and Qualcomm in Joint Investment on SMIC's New Research and Development Company

A Joint Collaboration is Set Up to Build China's Most Advanced Integrated Circuit Research and Development Platform. The current focus will be on **developing 14nm logic technology.**

Source: Semiconductor Engineering :: What China Is Planning

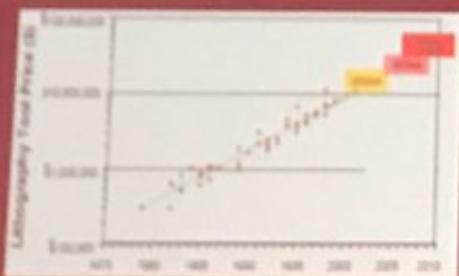
Specialized processors/accelerators

IBM

Simultaneous Shift in Computing Models

Patchwork of Extensions To Address the Cost of Scaling to New Workloads!

Tough Economics of CMOS scaling



End of frequency scaling

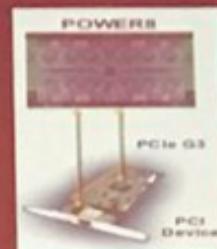


CPU
Centric

Accelerator
Centric

FPGA

GPU



Traditional Accelerators
improve energy efficiency and
extend scaling

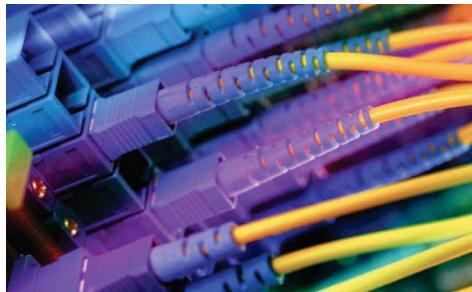


200 CPUs



10 CPUs +
20 accelerators

Beyond Moore's Law Photonics

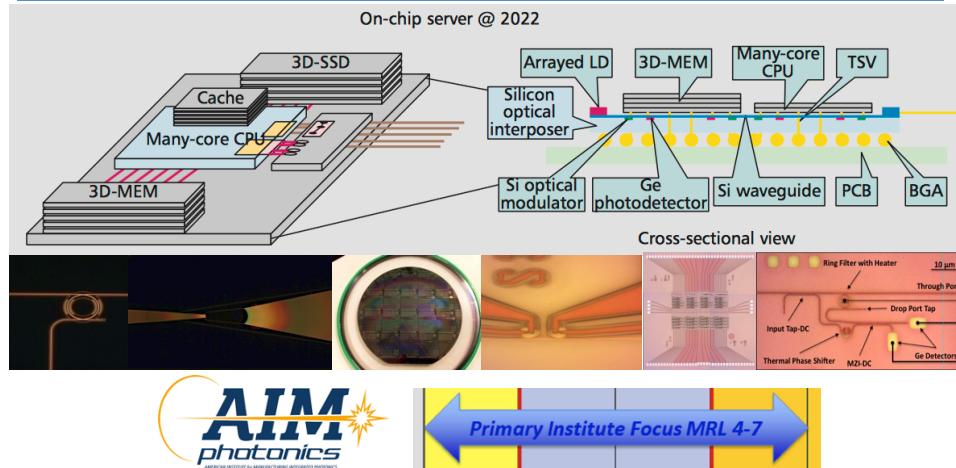


- $\rightarrow \$1/\text{Gb/s}$
- 25 pJ/bit

Both Too High

Today's Petascale computing utilize optical transceivers for the 'network' interconnect

5 -10 years: Commodity Integrated Photonics

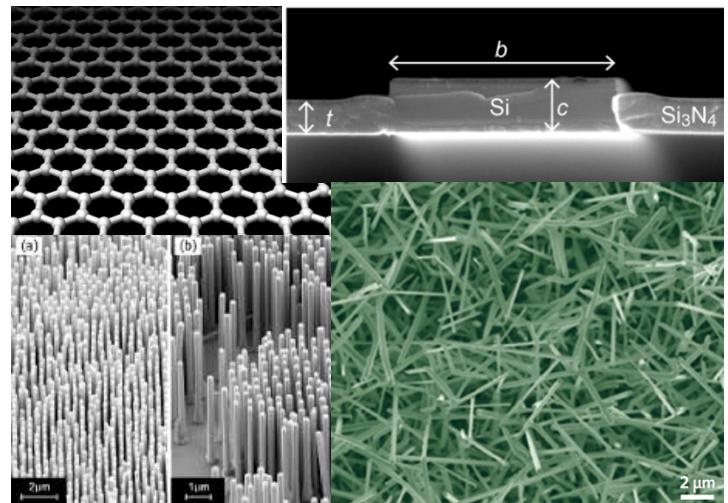


Primary Institute Focus MRL 4-7

- Hetero-Integrated CMOS photonics manufacturing
- Drastically lower the cost of packaging
- Higher data rate per optical IO, further reduction
- $25 \text{ pJ/bit} \rightarrow < 1 \text{ pJ/bit}$ optics total ($> 25X$)
- $\$1/\text{Gb/s} \rightarrow 10\text{¢ Gb/s} (\$100/\text{Tb/s})$ ($10X$)

10-20 years: Need "Beyond Moore" Photonics

- **Scale Energy and Cost by 10^4**
 - $\rightarrow 1 \text{ fJ/bit}$ optics complete ($> 25,000X$ equivalent)
 - $\rightarrow 0.01\text{¢ Gb/s} (\$10\text{¢/Tb/s})$ ($> 10,000X$ equivalent)
- **New Materials, Devices, Components**



- **Interface to LV-CMOS and beyond-Moore's transistor devices**
 - TFETs, Quantum, Neuromorphic, etc.
- **Optical switching, routing, computing**
- **Optical modeling infrastructure**
 - Optical materials, devices \rightarrow sub-systems \rightarrow application impact